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APPLICATION NO	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO	CONFIRMATION NO
09 771,673	01/29/2001	Hessel Sprey	NEDER23.001CP1	8115
20995	2590 12.10.2002			
KNOBBE MARTENS OLSON & BEAR LLP			FXAMINER	
2040 MAIN STREET FOURTEENTH FLOOR IRVINE, CA 92614		MACARTHUR, SYLVIA		
			ART UNIT	PAPER NUMBER
			1763	Ã

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	09/771,673	SPREY ET AL.				
Office Action Summary	Examiner	Art Unit				
	Sylvia R MacArthur	1763				
The MAILING DATE of this communicati Period for Reply	ion appears on the cover sheet wi	th the correspondence address				
A SHORTENED STATUTORY PERIOD FOR THE MAILING DATE OF THIS COMMUNICAL Extensions of time may be available under the provisions of 37 after SIX (6) MONTHS from the mailing date of this communical	TION. CFR 1 136(a) In no event, however, may a reation	eply be timely filed				
 If the period for reply specified above is less than thirty (30) day If 1/O period for reply is specified above, the maximum statutor Falure to reply within the set or extended period for reply will. Any reply received by the Office later than three months after the earned patent term adjustment. See 37 CFR 1 704(b) 	y period will apply and will expire SIX (6) MON by statute, cause the application to become AB	THS from the mailing date of this communication ANDONED (35 U.S.C. § 133)				
Status						
1) Responsive to communication(s) filed of	on <u>29 January 2001 and 07 Octo</u>	<u>ber 2002</u> .				
2a) This action is FINAL . 2b)	☐ This action is non-final.					
3) Since this application is in condition for closed in accordance with the practice						
Disposition of Claims						
4) Claim(s) 11-20 is/are pending in the application.						
4a) Of the above claim(s) <u>11-14</u> is/are withdrawn from consideration.						
5) Claim(s) is/are allowed.						
6) Claim(s) 15-20 is/are rejected.						
7) Claim(s) is/are objected to.						
8) Claim(s) are subject to restriction Application Papers	and/or election requirement.					
<u> </u>	raminor					
9) The specification is objected to by the Ex10) The drawing(s) filed on 29 January 2001		cted to by the Evaminer				
Applicant may not request that any objection						
11) The proposed drawing correction filed on						
11) The proposed drawing correction filed on is: a) approved b) disapproved by the Examiner. If approved, corrected drawings are required in reply to this Office action.						
12) The oath or declaration is objected to by the Examiner.						
Priority under 35 U.S.C. §§ 119 and 120	TO EXAMINATE					
13) Acknowledgment is made of a claim for	foreign priority under 35 H.S.C. 8	S 119(a)-(d) or (f)				
a) All b) Some * c) None of:						
1. Certified copies of the priority documents have been received.						
Certified copies of the priority documents have been received in Application No						
3. Copies of the certified copies of th						
	nal Bureau (PCT Rule 17.2(a)).					
14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).						
a) The translation of the foreign langua	ade provisional application back.	T + 14				
Notice of Draftsperson's Patent Drawing Review (PTO-5) information Disclosure Statement(s) (PTO-1449) Paper		r furma. Patent Application (970, 152)				

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DETAILED ACTION

Election/Restrictions

- 1. Restriction to one of the following inventions is required under 35 U.S.C. 121:
 - Claims 11-14, drawn to a method for etching a substrate, classified in class 216, subclass 73.
 - Claims 15-20, drawn to an apparatus for etching a substrate, classified in class
 subclass 345.33.

The inventions are distinct, each from the other because of the following reasons:

- 2. Inventions I and II are related as process and apparatus for its practice. The inventions are distinct if it can be shown that either: (1) the process as claimed can be practiced by another materially different apparatus or by hand, or (2) the apparatus as claimed can be used to practice another and materially different process. (MPEP § 806.05(e)). In this case the apparatus can be used to practice another method, i.e. one where both valves open simultaneously. These are statements of intended use and are not withstanding.
- 3. Because these inventions are distinct for the reasons given above and have acquired a separate status in the art as shown by their different classification, restriction for examination purposes as indicated is proper.
- 4. During a telephone conversation with Martin Hellebrandt on December 6, 2002 a provisional election was made with traverse to prosecute the invention of the apparatus, claims 15-20. Affirmation of this election must be made by applicant in replying to this Office action.

 Claims 11-14 are withdrawn from further consideration by the examinar 37 CER 1-142(b).

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Claim Rejections - 35 USC § 102

5. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

6. Claims 15, 17, and 18 are rejected under 35 U.S.C. 102(b) as being anticipated by Tohru et al (EPO 0335313).

Tohru teaches a method and apparatus for manufacturing a semicondcutor device. Tohru discusses an etching chamber (quartz tube 10), discharging chamber 14 (auxiliary chamber). Etchant 14A and catalyst 14B are introduced into the etching chamber via the auxiliary chamber positioned within a first path (17). Etchant 10A and catalyst 10B are positioned within a second path. The etching chamber is exhausted using exhaust pump 12. A plurality of shut-off valves is shown along the pipelines in Fig.1. The lines to the etching chamber are flushed via the auxiliary chamber. The open/closed state of the shut-off valves is a matter of intended use, which does not merit patentable weight.

7. Claims 15, 16, 18, and 19 are rejected under 35 U.S.C. 102(b) as being anticipated by Izumi et al (USP 5,022,961).

Izumi teaches a method of etching a film comprising HF and an alcohol as etchants and nitrogen as the catalyst. The bubbler illustrated in Fig. 1 is the auxiliary chamber. The reaction chamber is illustrated therein as element 12. A plurality of (shut-off) valves is illustrated as well as bypass line 18. Note when the valve of line 26 is shut off the auxiliary chamber is by-passed

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lines 8-15.1zumi further teaches that the etching chamber 12 is formed with Teflon as it has particularly excellent characteristics in resistance to HF. The open closed state of the shut-off valves is a matter of intended use, which does not merit patentable weight.

Claim Rejections - 35 USC § 103

- 8. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 9. Claim 20 is rejected under 35 U.S.C. 103(a) as being unpatentable over Izumi in view of Mayer et al (USP 6,333, 275).

The teaching of Izumi were discussed above.

Izumi fails to teach that the etching chamber comprises polyvinylidene fluoride (PVDF).

Mayer teaches the advantages utilizing such plastics as PVDF as a material of construction in harsh corrosive environments. In col. 12 lines 4-13, Izumi discusses the motivation to utilize plastics such as PVDF. Therein it is discussed that PVDF is resist to chemical attack and has sufficient mechanical strength (without creep or flow) to maintain necessary stringent mechanical tolerances.

Thus, it would have been obvious for one of ordinary skill in the art at time of the claimed invention to utilize PVDF as the material of construction for the etching chamber.

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10. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Sylvia R MacArthur whose telephone number is 703-306-5690. The examiner can normally be reached on M-F during the core hours of 8 a.m. and 2 p.m.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Gregory L. Mills can be reached on 703-308-1633. The fax phone numbers for the organization where this application or proceeding is assigned are 703-872-9310 for regular communications and 703-872-9311 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0661.

Sylvia R. MacArthur December 9, 2002

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